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(54) **PLUG, METHOD OF MANUFACTURING  
PLUG, AND MEMBER FOR  
SEMICONDUCTOR MANUFACTURING  
APPARATUS**

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(71) Applicant: **NGK INSULATORS, LTD.**,  
Nagoya-City (JP)

(72) Inventors: **Hideaki HASHIMOTO**, Nisshin-Shi  
(JP); **Masashi ONO**, Nagoya-Shi (JP);  
**Michihiro ASHIDA**, Nagoya-Shi (JP)

(57)

**ABSTRACT**

(73) Assignee: **NGK INSULATORS, LTD.**,  
Nagoya-City (JP)

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A plug includes a plug body, a spiral gas flow path that is provided in the plug body and that extends from a lower surface of the plug body to an upper surface, and at least one branch path that branches from a position on the spiral gas flow path and that opens on an outer circumferential surface of the plug body or that is in communication with another spiral gas flow path that differs from the spiral gas flow path and that extends from a lower surface of the plug body to an upper surface.

